

INFORMATION CITED BY APPLICANT(S) THAT MAY BE MATERIAL TO THE
PROSECUTION OF THE SUBJECT APPLICATION

Applicant: F.M. Schellenberg et al. Attorney Docket No. MEGC122529
Application No.: -- Group Art Unit: --
Filed: March 26, 2004 Examiner: --
Title: CREATING PHOTOLITHOGRAPHIC MASKS

U.S. PATENT DOCUMENTS

*Examiner Initial	ID	Document No.	Date	Name
<i>PS</i>	U1	5,364,716	11/15/1994	Nakagawa et al.
	U2	5,573,890	11/12/1996	Spence
	U3	5,636,131	06/03/1997	Liebmann et al.
	U4	5,663,017	09/02/1997	Schinella et al.
	U5	5,702,848	12/30/1997	Spence
	U6	5,766,804	06/16/1998	Spence
	U7	5,766,806	06/16/1998	Spence
	U8	5,807,649	09/15/1998	Liebmann et al.
	U9	5,858,580	01/12/1999	Wang et al.
	U10	5,867,401	02/02/1999	Haruki
	U11	6,132,908	10/17/2000	Shiraishi et al.
	U12	6,493,866	12/10/2002	Mayhew
	U13	6,503,666	01/07/2003	Pierrat
	U14	6,524,752	02/25/2003	Pierrat
<i>PS</i>	U15	2002/0129327	09/12/2002	Pierrat et al.

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FOREIGN PATENT DOCUMENTS

*Examiner Cite Initial	No.	Document No.	Kind Code	Publication Date (mm/dd/yyyy)	Country	English	
						Abstract Provided	Translation Provided
<u>BF</u>	F1	DE 41 21 564	A1	01/09/1992	Germany		
<u>BF</u>	F2	EP 0 698 916	A2	02/28/1996	EPO		
<u>BF</u>	F3	WO 99/14636	A1	03/25/1999	PCT		

OTHER INFORMATION

(Including Author, Title, Date, Pertinent Pages, Etc.)

*Examiner Initial	ID	
<u>BF</u>	O1	Marc D. Levenson, <i>Improving Resolution in Photolithography with a Phase-Shifting Mask</i> , IEEE TRANSACTIONS ON ELECTRON DEVICES, Vol. ED-29, No. 12, December 1982.
<u>BF</u>	O2	Hideyuki Jinbo and Yoshio Yamashita, <i>Improvement of Phase-Shifter Edge Line Mask Method</i> , Japanese Journal of Applied Physics, Vol. 30, No. 11B, November 1991, pp. 2998-3003.
<u>BF</u>	O3	Kazuyuki Inokuchi, Tadashi Saito, Hideyuki Jinbo, Yoshio Yamashita, and Yoshiaki Sano, <i>Sub-Quarter Micron Gate Fabrication Process Using Phase-Shifting Mask for Microwave GaAs Devices</i> , JAPANESE JOURNAL OF APPLIED PHYSICS, Vol. 30, No. 12B, December 1991, pp. 3818-3821.
<u>BF</u>	O4	B. J. Lin, <i>Phase-Shifting Masks Gain an Edge</i> , IEEE CIRCUITS & DEVICES, March 1993, pp. 28-35.
<u>BF</u>	O5	Marc D. Levenson, <i>Wavefront Engineering for Photolithography</i> , PHYSICS TODAY, July 1993.

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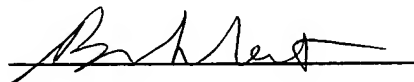
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Initial ID

12/10 O6 Harafuji, Kenji et al., "A Novel Hierarchical Approach for Proximity Effect Correction in Electron Beam Lithography," IEEE Transaction on Computer-Aided Design of Integrated Circuits and Systems, *IEEE* 12(10):1508-1514, New York, October 10, 1993.

Examiner

Date Considered



12/20/05

*Examiner: Initial if reference considered, whether or not citation is in conformance with M.P.E.P. § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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